

Preparation of metal oxide thin films from organic-additive-free aqueous solutions by low-speed dip-coating

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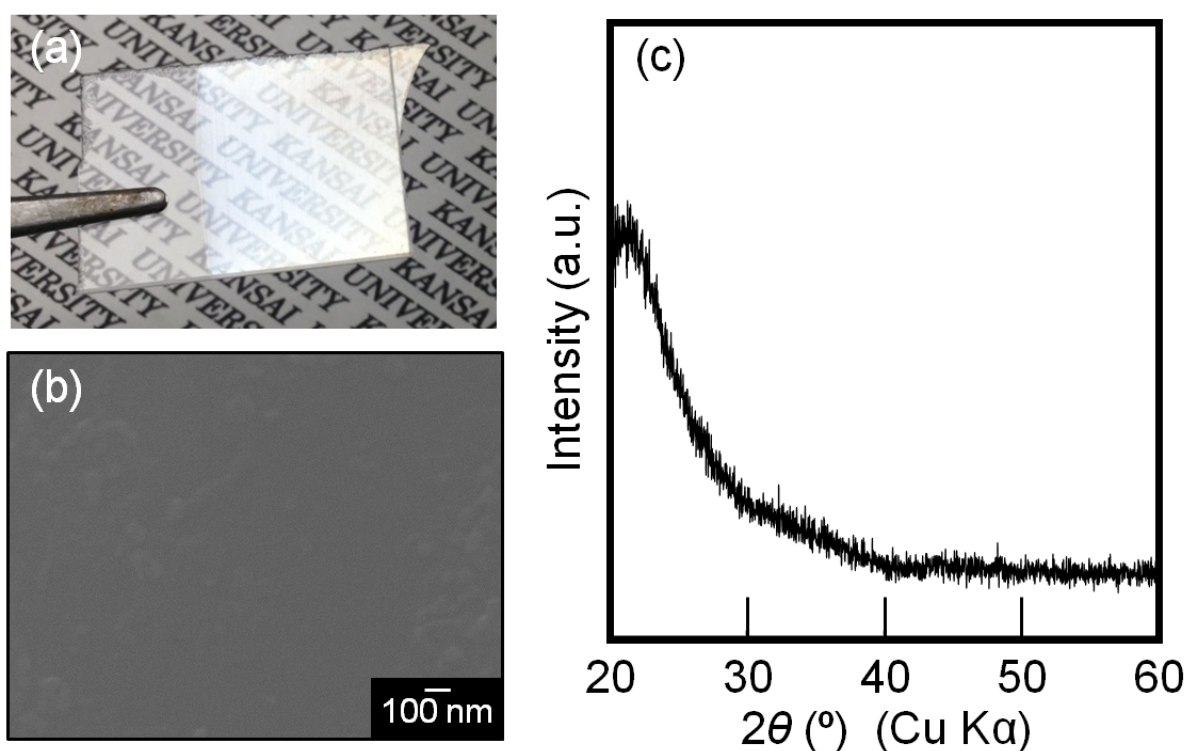


Fig. S1 Optical micrograph (a), SEM image (b) and XRD pattern of the SnO₂ precursor film prepared with one-time dip-coating at 0.2 cm min⁻¹ in a thermostatic oven at 60 °C.

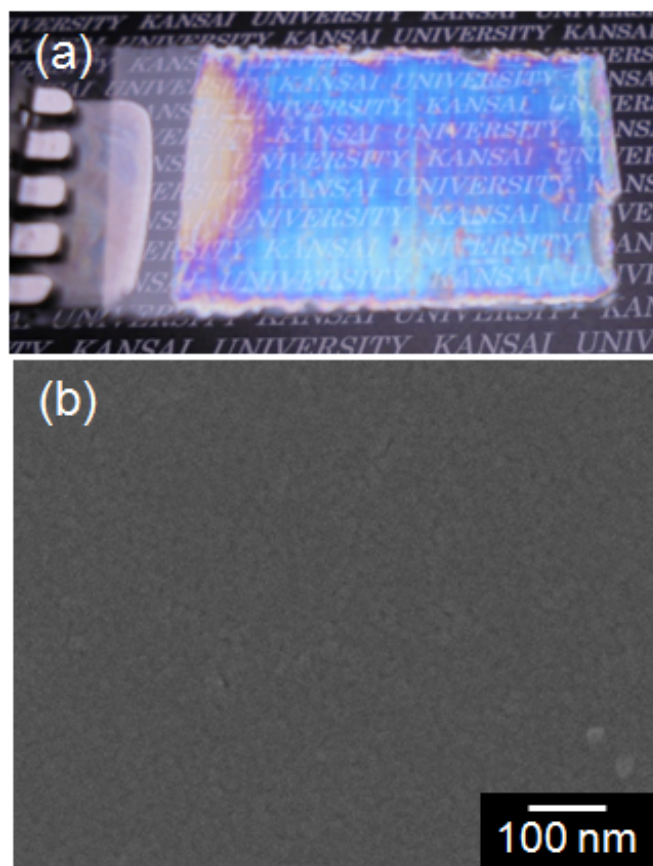


Fig. S2 Optical micrograph (a) and SEM image (b) of the heat treated TiO_2 film prepared with one-time dip-coating at 0.2 cm min^{-1} in a thermostatic oven at 40°C .

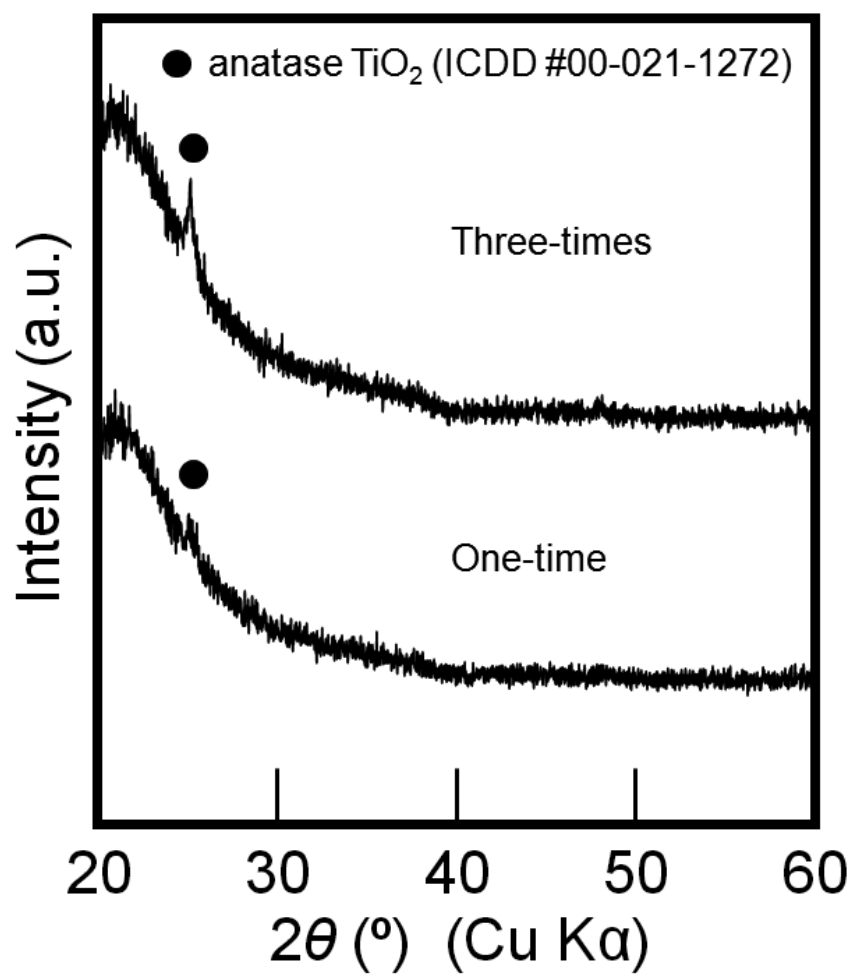


Fig. S3 XRD patterns of the heat treated TiO₂ film prepared with one- and three-times dip-coating at 0.2 cm min⁻¹ in a thermostatic oven at 40 °C